

ELECTROCRAMICS LABORATORY

Analytical and non-analytical instruments



NON-ANALYTICAL INSTRUMENTS



Electric resistance furnace Introduction

Electric resistance furnaces are of the indirect type by which electric energy is converted into heat as a current flows through the heating elements. These furnaces can be used for heat treatment, sintering, calcination, annealing, and etc. Resistance furnaces provide higher temperatures, more uniform temperature distribution, ease of automation and temperature control. Additionally these furnaces are more safe than many other types of furnaces.



Compaction direction is normal to sheet surface

Microstructure and texture evolution of a powder specimen subjected to sintering in different temperatures







Schematic presentation of microstructural evolution during sintering



Device: Resistance furnace Manufacturer: *AZAR/NFE1700R-3DH*



Technical specification

	1.1		1.11			${\bf r} = {\bf r}$	1.1	1.1	1.1		14141
Maxim	ım	ten	iper	atur	e					1640	°C
	11.	1.1.	1.12	1.12	с. ÷.	$\{ i, j \}$	1.1	111	11.1	1.1.1.1	1111
Capacit	y									3 L	

Device: Resistance furnace Manufacturer: EXCITON/Ex-1200-2L



Technical specification

Maximum temperature

Capacity

1000 °C

1L

aterials Scien

Shiraz Univer

Device: Resistance furnace Manufacturer: *EXCITON/EX-1200-4L*



Technical specification

Maximum	ten	npei	atu	re	j.	ł	ł		1	000	°C	ļ
Capacity			j.		ł.	ł		j.	2	L		ł

.

Device: Resistance furnace Manufacturer: *MAHAR/PCD33A*



Technical specification

1100 °C 8 L

Maxim	um	ı t	er	'nŗ	be	ra	tu	re		į	ł	ŝ	ŝ	ļ
Capacit	tv	ł	ł	ł	ł	ł	ł	ł	ł	ł	ł	ł	ł	ļ
Pass		- 12	- 12	12	11	12	11	11	12	11	12	11	11	λ.

Device: Resistance furnace Manufacturer: *MAHAR/PCD33A*



Technical specification

Maximum temperature 1000 °C Capacity 8 L * Equipped with NP200 controller

Device: Resistance furnace Manufacturer: *MAHAR/PCD33A*



Technical specification

z Umin

Shina

Maximum te	mper	ature			1460 °C
Capacity					8 L
* Equipped	with	NP20	0 cont	roller	

Device: Resistance furnace Manufacturer: *MAHAR/PCD33A*



Technical specification

Maximum temperature	1360 °C
Capacity	8 L
* Equipped with NP200 controller	

Device: Resistance furnace Manufacturer: *ATRA/AFE1400L-3DH*



Technical specification

Shina

Maximum	tempera	ture				1360 °
Capacity		222				3 L
	na na na na na	121212	1.1.1.	12121	. 1. 1.	anan anan an



Device: Horizontal tube furnace Manufacturer: *ATRA/ATE-1100L*



Technical specification

Maximum temperature Heating tube dimensions

length: 30 cm,

Diameter: 5 cm

900 °C

- * Providing the capability to use inert gas
- * PID control to program the temperature regime



Device: Cut off machine-precision cutter

Manufacturer: SANAT CERAM CO.

This lab is equipped with a high precision **cut off machine** for fine cutting of specimens. Cut off machines are used for cutting raw materials into their specified dimensions. In contrast to the typical saws such as the smaller portable ones, the cut off machine is an industrial-strength saw that is used for heavy and repeated use. Fine cutting of the ceramic specimens

Technical specification

* Providing rotation speed up to 50 rpm
* Increasing the cutting speed during the cutting process





Shina

Device: Glovebox

Manufacturer: BACKER/VBOX2-HIM



Shixaz University

A laboratory **glove box** is a sealed enclosure designed to create and maintain an environment where the air inside is filtered and replaced with sterile air. This allows for sensitive operations to be carried out without contamination.

Vacuum of the main container -0.999 bar									
Vacuum of the side chamber	-0.999999 bar								
Glove size	2 gloves, 60 cm								



Device: Laboratory oven Introduction

Laboratory ovens are standard equipment. found in most clinical, forensic, electronics, material processing, and. research laboratories. Laboratory ovens provide uniform temperature and precise temperature control for annealing, heating, baking, drying, curing, evaporating, sterilizing and other industrial laboratory functions. This lab is equipped with 3 ovens with different capabilities and special features which will be presented.



Schematic presentation of a laboratory oven



Shixaz University

Device: Regular laboratory oven

Manufacturer: *MEMMERT/800-100*



Technical specification

Maximum temperature	•	i.	i.		i.	i.	i.	i.	i.			i.	ł	i.	ł			2	50	0	С	
Temperature accuracy	li li	li li	li li	la La	li Li	li Li	li Li	li Li	li Li	li Li	i.	li Li	Ì	li li	Ì	Ì	Ì	ŧ	0.	5	°C	
* Programmable	i.	i.	ł	i.	i,	i.	i,	i.	i.	i.	į	i.	ł	i.	ł	ł	ł	ł	ł	i.	i.	ļ
*Equipped with a far	i) I	Ì	ł	la la	li li	li li	li li	la la	la la	ł	l	la la	Ì	Ì	Ì	Ì	Ì	ł	ł	la la	le Le	ļ



Device: Digital laboratory oven

Manufacturer: LABCON



Technical specification

Maximum temperature

250 °C

Shiyaz Univ

Device: Vacuum laboratory oven

Shiraz Uniw



Device: Autoclave

Manufacturer: NAZERKARAN INSPECTION & ENGINEERING CO.

Autoclaves are pressure vessels used to process parts and materials which require exposure to elevated pressure and temperature such as cure polymeric coatings and layers, vulcanize rubber, and hydrothermal synthesis.

Designed ter	npera	ture		ł	le le					le le				i.	le le	ł		20	00	PC	
Working pre	ssure			ŝ	į.	ġ		ł	ł	į.	ġ	ł		ł	ľ		i.	21	at	m	ł
Capacity			Ċ.	ł	ł.		Ċ.	ł	ł	ł.	ļ	j,	ġ	ł	ł	ł,	ł	9	L		į,



Device: Ultrasonic homogenizer

Manufacturer: AORAN/FS600N



Technical specification

Output power 6	600 w (0%-1	.00%	continuous	adjustable)
Frequency 2	0 kHz			
Capacity 2	0-500 ml			
Total working timer 1	s – 99 hour	s with	pause fund	ction

leaner

Device: Ultrasonic cleaner

Manufacturer: POWER SONIC/LUC-410



Time Range	1~99 min (Digital)
Temperature range	Ambient~70°C (Digital)
Frequency	40 kHz
Tank capacity	10.7 L

Device: Centrifuge

Manufacturer: POLE IDEAL TAJHIZ CO./UNIVERSAL 320





Technical specification

Maximum rotational speed	12000 rpm
Capacity	4 × 100
Maximum relative centrifugal force	21382
Time range	1-100min

* Equipped with impulse system for short term applications

Device: Centrifuge

Manufacturer: HETTICH/ROTOFIX 32A



Maximum rotational speed	4000 rpm
Capacity	4×100 ml or 15×32 m
Maximum relative centrifugal force	4226
Time range	1s – 99 min
* Equipped with impulse system for	short term applications

Device: Cold incubator

Manufacturer: PARSIAN TEB



Technical specification

Minimum temperature



laterials Science

Shiraz Universi



Department of Materials Science and Engineering

ANALYTICAL INSTRUMENTS

Device: Precision lab. balance

Manufacturer: KERN/ALS 220-4





Shiyaz Umive



Technical specification

Resolution			111				0.0001 g
Maximum w	eight						220 g
	1919-19	14.14	1919	1414	1919-19	1919-19	1. 1. 1. 1. 1. 1. 1. 1.





Resolution	į	j.	j.	j.	i.	ŝ	ŝ	j	ľ.	ł	ł	ł	0.01	g
Maximum weight	ł	ł	ł	l. L	ł	ł	l	ł	ł	ł	ł	ļ	300 g	5

Device: LCR meter

Manufacturer: ARMA



Technical specification

- * Measurement of inductance
- * Measurement of capacitance
- * Measurement of resistance



Device: pH meter

Manufacturer: METROHM/827



Technical specification

Measuring range Resolution Accuracy

pH: -8-22 / ±1200 mV 0.001 pH / 0.1 mV ±0.003 pH / ±0.2 mV